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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:
Cohen, et al.

Serial No.: 09/206,027

Filed: December 4, 1998

For: Plasma Preclean With Argon,
Helium, and Hydrogen Gases

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Group Art Unit: 1765

Examiner: L. Vinh

Assistant Commissioner for Patents
Washington, D.C. 20231

Dear Sir:

CERTIFICATE OF MAILING 37 CFR 1.8	
I hereby certify that this correspondence is being deposited on May 15, 2001 with the United States Postal Service as First Class Mail in an envelope addressed to: Assistant Commissioner for Patents, Washington, D.C. 20231.	
May 15, 2001 Date	<i>B. Todd Pattison</i> Signature

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RESPONSE TO OFFICE ACTION DATED FEBRUARY 5, 2001

In response to the Office Action dated February 5, 2001, having a shortened statutory period for response extended one month to June 5, 2001, please enter the following amendments and reconsider the claims pending in the application for reasons discussed below.

IN THE CLAIMS:

Please replace the following claims:

C1 1. (Amended) A method for processing a substrate in a processing chamber, comprising exposing a patterned substrate surface to a plasma generated from a gas mixture consisting of argon, helium and hydrogen, wherein the gas mixture comprises less than about 75% by volume of argon.

C2 3. (Amended) The method of claim 1, wherein the hydrogen is provided to the processing chamber in a mixture of about 95% by volume of helium and about 5% by volume of hydrogen.